## EDTM2020 - Preliminary Advance Program

As of January 29, 2020

	- Mond	ay, Ma	rch 16			As of January 29, 2020		
08:00-08 Opening Chair:	Remarks Samar Sa			Main Room (Matahari I, II, III)				
08:30-10				Main Room (Matahari I, II, III)				
Plenary S Chair:	Session 1 Arokia N	lathan						
8:30	9:15	PL-1		The Forever Exponential? Moore's Law: Past, Present and Future	Kaizad Mistry	Intel Corporation		
9:15	10:00	PL-2		Semiconductor Nanowires for Optoelectronics Applications	Chennupati Jagadish	The Australian National University		
10:00	10:45	PL-3		Rapid Yield Improvement Using Intelligent Data Mining	Vivek Jain	Maxim Integrated		
10:45-11		otion		Main Room (Matahari I, II, III)				
Chair:	rs Present Aabid H		hiruddin	Haji Hamdan				
11:15-12 Lunch Br				Rooms Etoile and Grand Ballroom II				
12:15-14				Room A (Matahari I)				
Session			Carla D	Focus Session 1: Thin-Film Transistor				
Chairs: 12:15	Naoto H 12:40	1A-1	Invited	Co-Design Between Semiconductor, Low-Variation Fully-Additive Printed/Flexible	Joseph Chang	NTU		
12:40	13:05	1A-2		Printing and Variation-Tolerant Digital Circuit Design Contact Printed ZnO Nanowires based FET for Large Area Electronics	Ravinder Dahiya	University of Glasgow		
13:05	13:30	1A-3		Printable Low Power Organic Transistor for Highly Customizable IoT Devices	Xiaojun Guo	Shanghai Jiao Tong University		
13:30	13:55	1A-3		Ultralow-Power All-Inkjet-Printed Organic Thin-Film Transistors for Wearables	Chen Jiang	University of Cambridge		
13:55			Invited	Systematic Defect Manipulation in Metal Oxide Semiconductors Towards High-	-			
15.55 14:20-14	14:20	1A-5	Invited	Performance Thin-Film Transistors Authors' Interview / Poster Viewing / Coffee Break	Yuqing Zhang	Peking University Shenzhen		
12:15-14				Room B (Matahari III)				
Session Chairs:	1B Anupam	Mitra, B		Nanotechnology Materials and Manufacturing Nguyen				
12:15	12:40	1B-1	Invited	Engineering Nanomaterials and Nanostructures for Electronic Applications: A Case Study of Carbon Nanotubes for Memory Devices	Rahul Sen	Nantero, Inc.		
12:40	13:05	1B-2	Invited	Manufacturing of Super Growth Carbon Nanotubes and Its Aqueous Solution for Electronic Devices	Shigemi Murakawa	Zeon Corporation		
13:05	13:30	1B-3		Performance and Reliability Improvement in Ge nMOSFETs with Different Surface Orientations Through Channel Flattening Process	Wen Hsin Chang	National Institute of Advanced Industrial Science and Technology (AIST)		
13:30	13:55	1B-4	Invited	Atomic Layer Defect-free Top-down Process for Future Nano-devices	Seiji Samukawa	Tohoku University		
13:55	14:20	1B-5		Back Gate Tunable Thin Film a-Si Nanowire BioFET for pH Detection by Compatible	Nawaz Shafi	Malaviya National Institute of Technology		
14:20-14	:40			CMOS Fabrication Process Authors' Interview / Poster Viewing / Coffee Break		Jaipur		
12:15-14 Session	:20 1C			Room C (Grand Ballroom I) Density Functional Theory-Based Simulation				
Chairs:	Risho Ko	h, Dipan	kar Pran					
12:15	12:40	1C-1	Invited	RSDFT-NEGF Quantum Transport Simulation of Ultra-Small Field-Effect Transistors	Nobuya Mori	Osaka University		
12:40	13:05	1C-2	Invited	Engineering Atom Scale Defects in Materials for Future Electronic Devices	Dipankar Pramanik	DSPAN Solutions		
13:05	13:30	1C-3	Invited	Superlattice Based Optoelectronic Analogs for Spintronic Applications	Bhaskaran Muralidharan	IIT Bombay		
13:30	13:55	1C-4		Ab-initio Tight Binding Study on Defects in Armchair Silicene Nanoribbon Double Gate Field Effect Transistor	Rajesh Junghare	Visvasvaraya National Institute Of Technology		
13:55	14:20	1C-5		Impact of Interface Traps Induced Degradation on Negative Capacitance FinFET	Om Prakash	Karlsruhe Institute of Technology		
14:20-14				Authors' Interview / Poster Viewing / Coffee Break				
12:15-14 Session	:20 1D			Room D (Grand Ballroom III) Power and RF Devices				
Chairs:	Saptarsh	i Das, Ch	un-Jung					
12:15	12:40	1D-1	Invited	Applications of Oxygen Inserted Silicon Devices in Power and RF	Robert J Mears	Atomera Incorporated		
12:40	13:05	1D-2		3-Dimensional 4H-SiC MOSFETs for Harsh Environment Electronics	Muhammad Idzdihar Bin Idris	FKEKK		
13:05	13:30	1D-3	Invited	Growth-Microstructure-Device Performance Correlations for III-nitride Optoelectronic and Power Devices on Sapphire and Silicon	Srinivasan Raghavan	Indian Institute of Science & Centre for Nano Science and Engineering		
13:30	13:55	1D-4		The Benefits of Using SiN as a Buried Oxide in Germanium-On-Insulator Substrate	Sethavut Duangchan	King Mongkut's University of Technology North Bangkok		
13:55	14:20	1D-5	Invited	A Microscopic "Toy" Model of Ferroelectric Negative Capacitance	Michael Hoffmann	NaMLab gGmbH/TU Dresden		
14:20-14	:40	•	•	Authors' Interview / Poster Viewing / Coffee Break	-			

Dave 1	Mand	ov Me	rah 16			As of January 29, 2020			
	· Mond	ay, Ma	rch 16						
14:40-16				Room A (Matahari I)					
Session Chairs:		VII Koiur	Via	GaN and III-V Devices					
		Vu, Kejur	I Ald	Low Leakage Mg-compensated GaN Schottky Diodes on Free-Standing GaN	[				
14:40	15:05	2A-1		Substrate for High Energy Alpha-Particle Detection	Abhinay Sandupatla	Nanyang Technological University			
15:05	15:30	2A-2		Low Interface Trap Density in AlGaN/GaN Metal-Insulator-Semiconductor High- Electron-Mobility Transistors on CVD-Diamond	Kumud Ranjan	Nanyang Technological University			
15:30	15:55	2A-3		Change of High-Voltage Conduction Mechanism in Vertical GaN-on-GaN Schottky Diodes at Elevated Temperatures	Abhinay Sandupatla	Nanyang Technological University			
15:55	16:20	2A-4		Modeling and Characterization of InAs Quantum-Well Metal-Oxide-Semiconductor Field Effect Transistors on Quartz for 1.0 THz Wave Detection	Tanemasa Asano	Kyushu University			
16:20	16:45	2A-5		Compact Modeling of Negative Capacitance Nanosheet FET Including Quasi-Ballistic Transport	Amol Gaidhane	IIT Kanpur			
16:45-17	:05			Authors' Interview / Poster Viewing / Coffee Break					
14:40-16	:45			Room B (Matahari III)					
Session	ession 2B			Large Area and Flexible Electronics					
Chairs:	Xiaojun	Guo, Yao	Jen Lee						
14:40	15:05	2B-1	Invited	Performances of Self-Aligned Top-Gate a-IGZO TFTs with Ultrathin PECVD SiO2 Gate Dielectric	Yuqing Zhang	Peking University Shenzhen			
15:05	15:30	2B-2	Invited	High Performance Printed Electronics on Large Area Flexible Substrates	Mahesh Soni	University of Glasgow			
15:30	15:55	2B-3	Invited	Fully Printed Vertical Transport Edge FETs for High Power Oxide Electronics	Subho Dasgupta	Indian Institute of Science (IISc), Bangalore			
15:55	16:20	2B-4		Printing Quasi-1D Nanomaterials for Large-Area Flexible UV Photodetectors	Fengyuan Liu	University of Glasgow			
16:20	16:45	2B-5		Self-Healing Interconnects for Flexible Electronics	Virendra Parab	Indian Institute of Science			
16:45-17	:05			Authors' Interview / Poster Viewing / Coffee Break					
14:40-16 Session				Room C (Grand Ballroom I) TCAD-1					
Chairs:		Sinah Cha	auhan. N	lobuya Mori					
14:40	15:05	2C-1		Particle-based Device Modeling	Sima Dimitrijev	Griffith University			
15:05	15:30	2C-2		Growth and Kinetics of Elemental and Binary Semiconducting Nanowires	Dhayalan Shakthivel	University of Glasgow			
15:30	15:55	2C-3		Significance of L-valley Charges and a Method to Include It in Electrostatic Model of III-V GAA FETs	Mohit Ganeriwala	Indian Institute of Technology Gandhinagar			
15:55	16:20	2C-4		Virtual Process-Based Spacer & Junction Optimization for an Inverter Circuit	Sofiane Guissi	Regional Technical Group of Lam Reserach & Lam Research			
16:20	16:45	2C-5	Invited	Electromigration Behavior of First-level Interconnection: Copper Pillar and Copper Stud	Christine Hau-Riege	Qualcomm Technologies, Inc.			
16:45-17	:05			Authors' Interview / Poster Viewing / Coffee Break					
14:40-16	:45			Room D (Grand Ballroom III)					
	ession 2D			Design and Technology					
Chairs:	William	(Bill) Nel	nrer, Ton	nasz Brozek Terebeneget Manufacturian Challanger (m. G. and 20. Matarial Broad Naga and					
14:40	15:05	2D-1	Invited	Technology and Manufacturing Challenges for Si and 2D Material Based Nano-scale Devices and Systems	Irfan Saadat	Khalifa University			
			1	Near Threshold Design Technology Optimization in 12LP Process	Navneet Jain	GlobalFoundries, Inc.			
15:05	15:30	2D-2							
	15:30 15:55	2D-2 2D-3	Invited	An agile and scalable manufacturing model to support 5G growth	Luis Andia	Soitec Microelectronics Singapore Pte. Ltd.			
15:05 15:30 15:55			Invited						
15:30	15:55	2D-3		An agile and scalable manufacturing model to support 5G growth	Luis Andia	Ltd.			

Day 1	Mond	av Ma	rch 16			As of January 29, 2020			
	Day 1 - Monday, March 16								
17:05-18:45 Session 3A				Room A (Matahari I) GaN Power Devices					
Chairs:		d Karmal	lkar, Wai	Tung Ng					
17:05	17:30	3A-1	Invited	Vertical Gallium Oxide Transistors with Current Aperture Formed Using Nitrogen-Ion Implantation Process	Masataka Higashiwaki	National Institute of Information and Communications Technology			
17:30	17:55	3A-2		Quasi-Normally-Off AlGaN/GaN HEMTs with Strained Comb Gate for Power Electronics Applications	Weichih Cheng	Hong Kong University of Science and Technology			
17:55	18:20	3A-3		Study on the Optimization of Off-State Breakdown Performance of p-GaN HEMTs	Fanming Zeng	Southern University of Science and Technology			
18:20	18:45	3A-4	Invited	Simulation and Design of Step-Etched Junction Termination Extensions for GaN Power Diodes	Jeramy Dickerson	Sandia National Laboratories			
18:45-19	:00			Authors' Interview					
Session				Room B (Matahari III) 2.5/3D Integration					
Chairs:		khilef, N		-					
17:05	17:30	3B-1	Invited	Low Temperature SmartCutTM Enabling 3D Integration	Walter Schwarzenbach	Soitec			
17:30	17:55	3B-2	Invited	Advanced Layer Transfer Technology of post-Si Materials for Heterogeneous Integration	Tatsuro Maeda	National Institute of Advanced Industrial Science and Technology (AIST)			
17:55	18:20	3B-3		Backstepping Position Control of High Frequency Piezoelectric Actuator Used in Ultrasonically Assisted Manufacturing	Mohammad Salah	The Hashemite University			
18:20	18:45	3B-4		The Investigation of Material Modification for SiO2, Si3N4 Film and Photo-resist Using High-Dose Ion Implantation Technique	Ryota Wada	Nissin Ion Equipment Co., Ltd.			
18:45-19				Authors' Interview					
17:05-18 Session				Room C (Grand Ballroom I) TCAD-2					
Chairs:		/ang, Vic	tor More						
17:05	17:30	3C-1		Comprehensive Design Solutions for Wide Bandgap Power Electronics	Tao Sun	Singapore & Silvaco SG			
17:30	17:55	3C-2		Modeling Thermal Behavior in Multi-layered GaN HEMT-like Structures	K. Nidhin	Indian Institute of Technology Madras			
17:55	18:20	3C-3	Invited	Misconception with Pad-Based CDM ESD Protection	Albert Wang	University of California, Riverside			
18:20	18:45	3C-4		Simulation and Device Characterization of the P+PN+P Junction Type Pinned Photodiode and Schottky Barrier Photodiode	Yoshiaki Hagiwara	AIPS			
18:45-19				Authors' Interview					
17:05-18 Session	:45 3D			Room D (Grand Ballroom III) Advanced Photovoltaic Devices and Detectors					
Chairs:	Juzar Va	si, Hang	Zhou		ſ				
17:05	17:30	3D-1		Optimization of Electron Transport Layers for High Performance Perovskite Solar Cells	Annie Ng	Nazarbayev University			
17:30	17:55	3D-2		Performance Enhancement of Double Quantum Well Solar Cell by Strain-Modulated Piezo-Phototronics Effect	Soumya Ranjan Routray	SRM Institute of Science and Technology			
17:55	18:20	3D-3	Invited	S-shape Current-Voltage Characteristics in Quantum Dot Integrated Multi-layer Organic Solar Cells	Upendra Verma	Indian Institute of Technology Roorkee			
18:20	18:45	3D-4		A Spectrum-Tunable and Flexible Light-Emitting Device with Ultra-Wide Wavelength Range	Guangya Jiang	Tsinghua University			
18:45-19				Authors' Interview					
19:00-21				Equatorial					
Poolside Reception									